

Inventor: Weimin Li et al.

Title: Compositions Of Matter and Barrier Layer Compositions

Assignee: Micron Technology, Inc.

**INFORMATION DISCLOSURE STATEMENT**  
**PURSUANT TO 37 C.F.R. " 1.56, 1.97 AND 1.98**

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

The listed references were cited by, or submitted to, the Office in the parent, co-pending application of the above-identified application. The above-identified application is a continuation application of co-pending application Serial No. 09/641,826, filed August 17, 2000. Such prior disclosure is sufficient for the above-identified application as far as copies of the references are concerned. 37 C.F.R. § 1.98(d) and MPEP § 609(2).

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: February 10, 2004

By: Jennifer J. Taylor  
Jennifer J. Taylor, Ph.D.  
Reg. No. 48,711

Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2497		Priority SERIAL NO. 09/641,826	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Weimin Li et al.			
				Priority FILING DATE August 17, 2000		GROUP Unknown	
U.S. PATENT DOCUMENTS							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
	AA	4,474,975	10/84	Clemons et al.			
	AB	5,962,581	10/99	Hayase et al.			
	AC	5,677,015	10/97	Hasegawa			
	AD	5,783,493	07/98	Yeh et al.			
	AE	5,807,660	09/98	Lin et al.			
	AF	4,833,096	05/89	Huang et al.			
	AG	5,405,489	04/95	Kim et al.			
	AH	5,470,772	11/95	Woo			
	AI	5,652,187	07/97	Kim et al.			
	AJ	5,656,337	08/97	Park et al.			
	AK	4,805,683	2/89	Magdo et al.			
	AL	5,874,367	2/99	Dobson			
	AM	5,858,880	1/99	Dobson et al.			
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes      No
	AN	0 942330	9/99	EPO			
	AO	9-50993	02/97	Japan			X
	AP	6-244172	09/94	Japan			X
	AQ	593,727	10/47	GB			
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AR		Withmall, R. et al., "Matrix Reactions of Methylsilanes and Oxygen Atoms", The Journal of Physical Chemistry, Vol. 92, No. 3, 1998,				
			pp. 594-602.				
	AS		Weidman, T. et al., "New Photodefinable Glass Etch Masks for Entirely Dry Photolithography: Plasma Deposited Organosilicon Hydride				
			Polymers", Appl. Phys. Lett., Vol. 62, No. 4, Jan. 25, 1993, pp. 372-374.				
	AT		Weidman, T. et al., "All Dry Lithography: Applications of Plasma Polymerized Methylsilane as a Single Layer Resist and Silicon				
			Dioxide Precursor", J. Photopolym. Sci. Technol., Vol. 8, No. 4, 1995, pp. 679-686.				
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	AA	5,219,613	6/93	Fabry et al.			
	AB	5,270,267	12/93	Ouellet			
	AC	5,541,445	7/96	Quellet			
	AD	6,022,404	02/00	Ettlinger et al.			
	AE	5,709,741	01/98	Akamatsu et al.			
	AF	4,648,904	03/87	DePasquale et al.			
	AG	4,158,717	06/79	Nelson			
	AH	5,667,015	09/97	Harestad et al.			
	AI	5,661,093	8/97	Ravi et al.			
	AJ	5,536,857	7/96	Narula et al.			
	AK	4,695,859	9/87	Guha et al.			
	AL	5,061,509	10/91	Naito et al.			
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes      No
	AM	5-263255	10/93	Japan			X
	AN	0 464515 A3	01/92	EPO			
	AO	0 771886 A1	05/97	EPO			
	AP	63-157443	06/88	JP			X
	AQ	0 471185 A2	02/92	EPO			
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			Microelectronic Engineering 30 (1996), pp. 275-278.				
	AS		Joshi, A. et al., "Plasma Deposited Organosilicon Hydride Network Polymers as Versatile Resists for Entirely Dry Mid-Deep UV				
			Photolithography", SPIE Vol. 1925 (1993), pp. 709-720.				
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			IEDM Tech. Dig., 1997, pp. 785-788.				
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	AA	4,600,671	7/86	Saitoh et al.			
	AB	5,753,320	5/98	Mikoshiba et al.			
	AC	5,356,515	10/94	Tahara et al.			
	AD	5,731,242	3/98	Parat et al.			
	AE	6,054,379	4/00	Yau et al.			
	AF	5,948,482	9/99	Brinker et al.			
	AG	5,800,877	9/98	Maeda et al.			
	AH	5,260,600	11/93	Harada			
	AI	4,992,306	2/91	Hochberg et al.			
	AJ	4,702,936	10/87	Maeda et al.			
	AK	4,863,755	9/89	Hess et al.			
	AL	5,234,869	8/93	Mikata et al.			
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	AM	0 588087 A2/3	03/94	EPO			
		9 055351	02/97	JP			
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	AN		Horie, O. et al., "Kinetics and Mechanism of the Reactions of O( <sup>3</sup> P) with SiH <sub>4</sub> , CH <sub>3</sub> SiH <sub>3</sub> , (CH <sub>3</sub> ) <sub>2</sub> SiH <sub>2</sub> , and (CH <sub>3</sub> ) <sub>3</sub> SiH", J. Phys. Chem. 1991, Vol. 95, pp. 4393-4400.				
	AO		McClatchie, S. et al., "Low Dielectric Constant Flowfill" Technology for IMD Applications", Proceed. of 3d Internatl. Dielectrics for ULSI Multilevel Interconnection Conf, Santa Clara, CA, Feb. 1997, pp. 34-40.				
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	AQ		Kiermasz, A. et al., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", DUMIC Conf., California, Feb. 1995, pp. 1-2.				
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	AA	5,302,366	4/94	Schuetz et al.			
	AB	5,591,494	1/97	Sato et al.			
	AC	5,968,611	10/99	Kaloyeros et al.			
	AD	6,159,871	12/00	Loboda et al.			
	AE	5,461,003	10/95	Havemann et al.			
	AF	6,124,641	9/00	Matsuura			
	AG	5,554,567	9/96	Wang			
	AH	6,028,015	2/00	Wang et al.			
	AI	5,744,399	4/98	Rostoker			
	AJ	5,883,014	3/99	Chen			
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							Yes    No
	AK	0 778496 A2	05/96	EPO			
	AL	06 067019A	03/94	JP (abstract)			
	AM	1172845 A2	01-2002	EPO			
	AN	08-213386A	08-1996	Japan			
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	AO		IBM Technical Disclosure Bulletin, "Low-Temperature Deposition of SiO <sub>2</sub> , Si <sub>3</sub> N <sub>4</sub> , or SiO <sub>2</sub> -Si <sub>3</sub> N <sub>4</sub> ", Vol. 28, Iss. 9, p. 4170 (Feb. 1986).				
	AP		TEXT: Ralls, K. et al., "Introduction to Materials Science and Engineering", 1976 John Wiley & Sons, Inc., pp. 312-313.				
	AQ		ABSTRACT: Loboda, M. et al., "Using Trimethylsilane to Improve Safety, Throughput and Versatility in PECVD Processes",				
			Electrochemical Society Meeting Abstract No. 358, 191 <sup>st</sup> Meeting, Montreal, Quebec, Vol. MA 97-1, 1997, page 454.				
	AR		Laxman, R. et al., "Synthesizing Low-K CVD Materials for Fab Use", Semiconductor Internatl., Nov. 2000, pp. 95-102 (printed from				
			www.semiconductor-intl.com).				
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	AA	6,017,779	1/00	Miyasaka			
	AB	6,156,674	12/00	Li et al.			
	AC	6,140,151	10/00	Akram			
	AD	5,314,724	5/94	Tsukune et al.			
	AE	5,376,591	12/94	Maeda et al.			
	AF	5,817,549	10/98	Yamazaki et al.			
	AG	6,072,227	6/00	Yau et al.			
	AH	6,001,741	12/99	Alers			
	AI	5,786,039	7/98	Brouquet			
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	AK	6,187,694 B1	2/01	Cheng et al.			
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							Yes      No
	AL	200068261A	03-2000	Japan			
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	AM		Anonymous, "New Gas Helps Make Faster ICs", Machine Design, Vol. 71, Iss. 21, Nov. 4, 1999, p. 118.				
	AN		Grant, J., "Hack's Chemical Dictionary", McGraw-Hill, Inc. 1969, Fourth Edition, page 27.				
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	AP		McKenzie, D.R. et al., "New Technology for PACVD", Surface and Coatings Technology, Vol. 82, pp. 326-333 (1996).				
	AQ		Shibata, N., "Plasma-Chemical Vapor-Deposited Silicon Oxide/Silicon Oxynitride Double-Layer Antireflective Coating for Solar Cells", Jap. Jour. of App. Physics, Vol. 30, No. 5, May 1991, pp. 997-1001.				
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	AB	6,114,255	9/00	Juengling			
	AC	6,238,976 B1	5/01	Noble et al.			
	AD	6,008,121	12/99	Yang et al.			
	AE	5,140,390	8/92	Li et al.			
	AF	5,286,661	2/94	de Fresart et al.			
	AG	6,184,151 B1	2/01	Adair et al.			
	AH	6,225,217 B1	5/01	Usami et al.			
	AI	6,004,850	12/99	Lucas et al.			
	AJ	6,140,677	10/00	Gardner et al.			
	AK	6,133,096	10/00	Su et al.			
	AL	6,136,636	10/00	Wu			
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	AM	368687A	09-1999	TW			
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	AN		Bencher, C. et al., "Dielectric Antireflective Coatings for DUV Lithography", Solid State Technology (March 1997), pp. 109-114.				
	AO		Dammel, R.R. et al., "Dependence of Optical Constants of AZ* BARLi™ Bottom Coating on Back Conditions, SPIE Vol. 3049 (1997), pp. 963-973.				
	AP		TEXT: Heavens, O.S., "Optical Properties of Thin Solid Films", pp. 48-49.				
	AQ		TEXT: Jenkins, F. et al., "Fundamentals of Optics", Properties of Light, pp. 9-10.				
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	AA	5,933,721	8/99	Hause et al.			
	AB	5,981,368	11/99	Gardner et al.			
	AC	6,159,804	12/00	Gardner et al.			
	AD	6,130,168	10/00	Chu et al.			
	AE	6,235,591 B1	5/01	Balasubramanian et al.			
	AF	6,198,144 B1	3/01	Pan et al.			
	AG	5,801,399	9/98	Hattori et al.			
	AH	5,994,730	11/99	Shrivastava et al.			
	AI	6,040,619	3/00	Wang et al.			
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	AL	6,451,504	09/02	Rolfson et al.			
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		Document Number	Date	Country	Class	Subclass	Translation
							Yes      No
	AM	429473A	04-2001	TW			
	AN	420844A	02-2001	TW			
	AO	8046186	02-1996	Japan			X
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
	AP		Wolf et al., "Silicon Processing for the VLSI Era - Vol. 1 - Process Technology," Prologue, page xxiii (2 pages total).				
	AQ		Wolf, "Silicon Processing for the VLSI Era, Vol. 2: Process Integration," © 1990, pp. 189-190.				
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	AQ	5,429,987	04-1995	Allen			
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	AR	8046188	02-1996	Japan			
	AS	7201716	08-1995	Japan			X
	AT	6232113	08-1994	Japan			
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	AE	5,710,067	01/98	Foote et al.			
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	AM	5,244,537	09-1993	Ohnstein			
	AN	6,204,168 B1	03-2001	Naik et al.			
	AO	4,562,091	12-1985	Sachdev et al.			
	AP	4,764,247	08-1988	Leveriza et al.			
	AQ	5,986,318	11-1999	Kim et al.			
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	AG	5,600,165	2/4/97	Tsukamoto et al.			
	AH	6,008,124	12/99	Sekiguchi et al.			
	AI	5,968,324	10/99	Cheung et al.			
	AJ	5,872,385	02/99	Taft et al.			
	AK	5,883,011	04/99	Lin et al.			
	AL	5,960,289	09/99	Tsui et al.			
	AM	4,755,478	07-1988	Abernathy et al.			
	AN	4,870,470	09-1989	Bass et al.			
	AO	5,312,768	05-1994	Gonzalez			
	AP	5,439,838	08-1995	Yang			
	AQ	6,001,747	12-1999	Annappagada			
	AR	6,518,122	02-2003	Chan et al.			
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							Yes    No
	AS						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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